# **Electrical and Computer Engineering Spring 2019**

# **ECE 730 Topic 10**

## ADVACNCED TECHNOLOGIES FOR SEMICONDUCTOR PROCESSING

Term:	Spring 2019
Instructor:	Prof. Siva Sivoththaman
Lecture hours:	
Room:	

## **COURSE DESCRIPTON:**

This course is intended to provide the students with the fundamentals, technological approaches, and practices in the fabrication of micro- and nano- electronic devices. Modern process technologies and design aspects for advanced devices will be covered along with the underlying theoretical concepts. Current device applications and future directions will also be discussed.

## **COURSE OUTLINE:**

#### Vacuum and Plasma Processes

Introduction to vacuum, introduction to plasmas, collision processes in plasmas, electrical characteristics of plasmas, dc glow discharges, RF discharges.

#### Thin Films and Deposition Processes

Physical and chemical vapor deposition; Atomic layer deposition; Plasma processes; Molecular beam and liquid phase epitaxy.

## **Plasma Etching Processes**

Role of etching in device fabrication; Modes of plasma etching; Etch chemistries; Reactive ion etching; Profile control in specific device structures.

#### **Fabrication of Nanostructures**

Top-down and bottom-up approaches; Zero-, one-, and two- dimensional structures; Nanoparticles and quantum dots; Nanotubes.

#### **Limits of Optical Lithography**

Optical lithography and its limits; Exposure techniques; Sub-micron processing.

#### **Nano-patterning**

Electron beam lithography; Nano-imprint lithography; Scanning probe techniques; Atomic scale manipulation.

## **Transistor fabrication and CMOS**

Processes for Junctions and Gate; Basics of MOS transistor fabrication; CMOS Process sequence; Layout design; Material implications.

## **Fabrication of Thin film devices**

Processes for thin film transistors; Circuit implementation; Display backplanes; Solar cells and photodetectors.

## Nanoelectronic device fabrication

Trends in future nanoelectronic devices and fabrication options; Quantum effect, tunneling, and single-electron devices

# **MARKING SCHEME**:

Project/assignments: 40%, Final exam: 60%

## **OTHER ACTIVITY**:

As part of the course, the students will take part in guided visits to nano- and micro- fabrication facilities on campus.

## **TEXT BOOK:**

**Course Notes**